

SUBSTRATE PROCESSING APPARATUS AND SUBSTRATE PROCESSING METHOD

ABSTRACT

A substrate processing apparatus and a substrate processing method that can improve the cleanliness of the substrate are provided. The substrate processing apparatus 1 of the present embodiment includes the rotation body 10 including the placement portion 13 to place the substrate W with the processed surface so that the space is maintained between the surface of the rotation body 10 facing the substrate W and the surface of the substrate W opposite the processed surface; the rotation driver 16 that rotates the rotation body 10, the liquid suppliers 30 and 40 that supply the processing liquid L1 and L2 on the processed surface of the substrate W, the cooler 20 that supplies the cooling gas G to the space between the substrate W and the placement portion 13, and the remover 90 that removes the droplet D on the surface of the rotation body facing the substrate W.

Fig.1